

ABSTRACT

A sputtering target containing a hexagonal laminar compound formed of indium oxide and zinc oxide and represented by $\text{In}_2\text{O}_3(\text{ZnO})_m$ wherein m is an integer of 2 to 7 and further contains 0.01 to 1 at% of an oxide of a third element having a normal valence of 4 or more, and a transparent electrically conductive film formed therefrom. The sputtering target has a low volume resistivity and permits stable sputtering. The transparent electrically conductive film is excellent in etchability.



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